

Based on years of experience with sputtering processes, ZSW tests sputter targets (e.g. $\text{ZnO:Al}_2\text{O}_3$) for industrial use, e.g. in thin-film solar cells. A standard method is used for the preconditioning of the targets, which are then tested up to high power levels. The sputtering quality is tested according to the tendency to arc formation, target pitting, and the attained film quality. Parameter variations (pressure, power etc.) and characterisation of the films are performed after consultation with the customers. Where appropriate, the films are also tested in complete film systems like CIS solar cells.

Requirements

Type PK500 cathode targets (488 mm x 88 mm)

Dual magnetron configuration for reactive deposition

